

Title (en)

DEVICE AND METHOD FOR TREATING SUBSTRATES

Title (de)

VORRICHTUNG UND VERFAHREN ZUM BEHANDELN VON SUBSTRATEN

Title (fr)

DISPOSITIF ET PROCEDE PERMETTANT DE TRAITER DES SUBSTRATS

Publication

**EP 1238411 A1 20020911 (DE)**

Application

**EP 00987373 A 20001208**

Priority

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Abstract (en)

[origin: WO0145143A1] In order to optimize flow conditions in a device (1) for treating substrates (2) in a treatment basin (3) that is filled with treatment fluid, said device comprising at least one diffuser (12) to introduce the fluid into the treatment basin (3), the distance between the diffuser (12) and the substrates (2) can be regulated. The invention also relates to a method for regulating said distance. According to an additional measure to improve flow conditions in said device, the diffuser (12) has a plate (18) that is curved cylindrically toward the substrates (2) and outlets (20), the cylindrical axes thereof extending perpendicularly in relation to the planes of the substrates.

IPC 1-7

**H01L 21/00**

IPC 8 full level

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CPC (source: EP KR US)

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Citation (search report)

See references of WO 0145143A1

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